

Supporting Information

Delamination/Rupture of Polycrystalline Diamond Film: Defining Role of Shear

Anisotropy

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Table 1S (supplementary information) provides a summary of deposition time periods and corresponding values of the film thicknesses.

Table 1S: Deposition parameters for the CVD diamond films used in the present study. Included are film thickness, temperature, pressure and deposition time.

Thickness	Temperature	Pressure	Deposition duration
12 μm	850°C	110 torr	12 h
18 μm	850°C	110 torr	18 h
21 μm	850°C	110 torr	21 h
30 μm	850°C	110 torr	30 h
32 μm	850°C	110 torr	32 h
34 μm	850°C	110 torr	34 h